

LITHOGRAPHIC APPARATUS, DEVICE MANUFACTURING METHOD,  
AND DEVICE MANUFACTURED THEREBY

In a lithographic apparatus the shape of the focal plane is adjusted using available manipulators in the projection lens system so that it is in closer conformity to the shape of the wafer surface in the exposure area. The control of the focal plane shape can be integrated with the leveling control which determines the height and tilt of the wafer surface.

[illegible]